

PATENT
Docket No. 474082002800

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the application of:

Nobumitsu TAKASE et al.

Serial No.: 10/512,405

Filing Date: June 15, 2005

For: HIGH-RESISTANCE SILICON WAFER
AND ITS MANUFACTURING
METHOD

Examiner: Jennifer M. Dolan

Group Art Unit: 2813

Confirmation No. 4607

AMENDMENT UNDER 37 CFR 1.111

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Action dated July 18, 2007, please amend this application as follows.

The listing of claims begins on page 2.

The Remarks begin on page 5.